CLAIMS

What is claimed is:

- 1. An imager cell comprising:
- 5 a photoreceptor;
 - a sense node; and
 - a pinned transfer gate disposed to transfer charge between the photoreceptor and the sense node.
 - 2. An imager cell as defined in claim 1, wherein the pinned transfer gate comprises a p-doped pinned region in an n-doped transfer region.
 - 3. An imager cell as defined in claim 1, further comprising a photoreceptor readout gate disposed above the photoreceptor.
 - 4. An imager cell as defined in claim 1, wherein the photoreceptor comprises a photogate.
- 15 5. An imager cell as defined in claim 1, wherein the photoreceptor comprises a photodiode.
 - 6. An imager cell as defined in claim 1, further comprising a reset transistor disposed to reset the sense node.
 - 7. An imager cell as defined in claim 1, further comprising an output amplifier coupled to the sense node.
 - 8. An imager cell as defined in claim 7, wherein the output amplifier is a source follower amplifier.
 - 9. An imager cell as defined in claim 3, further comprising a readout clock connection coupled to the photoreceptor readout gate.

- 10. An imager cell as defined in claim 9, further comprising control circuitry coupled to the readout clock connection, the control circuitry supplying a photoreceptor readout clock.
- 11. An imager cell as defined in claim 10, wherein the photoreceptor readout clock is characterized by a V+ level applied during an integration period, and a V- level applied during a transfer period.
- 12. An imager cell comprising:
 - a photoreceptor;
 - a sense node;
- a pinned transfer gate disposed to transfer charge between the photoreceptor and the sense node; and
- a photoreceptor readout gate disposed above the photoreceptor, the photoreceptor readout gate having material removed to form a photoreceptor readout gate light aperture above the photoreceptor, whereby the photoreceptor provides enhanced response to blue light.
- 13. An imager cell as defined in claim 12, further comprising a pinned aperture region under the photoreceptor readout gate light aperture.
 - 14. An imager cell as defined in claim 12, wherein the pinned transfer gate comprises a p-doped pinned region in an n-doped transfer region.
- 15. An imager cell as defined in claim 12, wherein the photoreceptor comprises a 20 photogate.
 - 16. An imager cell as defined in claim 12, wherein the photoreceptor comprises a photodiode.
 - 17. An imager cell as defined in claim 12, further comprising a reset transistor disposed to reset the sense node.

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- 18. An imager cell as defined in claim 12, further comprising an output amplifier coupled to the sense node.
- 19. An imager cell as defined in claim 18, further comprising an anti-reflective coating disposed above the photoreceptor.
- 5 20. An imager cell as defined in claim 12, further comprising a readout clock connection coupled to the photoreceptor readout gate.
 - 21. An imager cell as defined in claim 20, further comprising control circuitry coupled to the readout clock connection, the control circuitry supplying a photoreceptor readout clock.
 - 22. An imager cell as defined in claim 21, wherein the photoreceptor readout clock is characterized by a V+ level applied during an integration period, and a V- level applied during a transfer period.
 - 23. An imager cell comprising:
 - a photoreceptor;
 - a sense node;
 - a pinned transfer gate disposed to transfer charge between the photoreceptor and the sense node; and
 - a photoreceptor readout gate disposed above the photoreceptor, the photoreceptor readout gate characterized by a photoreceptor readout gate thickness of less than 2000 Angstroms, whereby the photoreceptor provides enhanced response to blue light.
- 20 24. An imager cell as defined in claim 23, wherein the photoreceptor readout gate thickness is less than 1000 Angstroms.
 - 25. An imager cell as defined in claim 23, wherein the photoreceptor readout gate thickness is less than 500 Angstroms.
 - 26. An imager cell as defined in claim 23, wherein the pinned transfer gate comprises a p-doped pinned region in an n-doped transfer region.

- 27. An imager cell as defined in claim 23, wherein the photoreceptor comprises a photogate.
- 28. An imager cell as defined in claim 23, wherein the photoreceptor comprises a photodiode.
- 5 29. An imager cell as defined in claim 23, further comprising a reset transistor disposed to reset the sense node.
 - 30. An imager cell as defined in claim 23, further comprising an output amplifier coupled to the sense node.
 - 31. An imager cell as defined in claim 28, wherein the output amplifier is a source follower amplifier.
 - 32. An imager cell as defined in claim 23, further comprising a readout clock connection coupled to the photoreceptor readout gate.
 - 33. An imager cell as defined in claim 32, further comprising control circuitry coupled to the readout clock connection, the control circuitry supplying a photoreceptor readout clock.
- 15 34. An imager cell as defined in claim 33, wherein the photoreceptor readout clock is characterized by a V+ level applied during an integration period, and a V- level applied during a transfer period.
 - 35. A method of manufacturing an imager cell, the method comprising: fabricating a photoreceptor in a semiconductor substrate;
- 20 fabricating a sense node in the substrate; and

fabricating a pinned transfer gate in the substrate disposed to transfer charge between the photoreceptor and the sense node.

36. A method as defined in claim 35, wherein fabricating the pinned transfer gate comprises fabricating an n-doped transfer region and fabricating a p-doped pinned region in the n-doped transfer region.

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- 37. A method as defined in claim 35, further comprising fabricating a photoreceptor readout gate disposed above the photoreceptor.
- 38. A method as defined in claim 35, wherein fabricating a photoreceptor comprises fabricating a photogate.
- 5 39. A method as defined in claim 35, wherein fabricating a photoreceptor comprises fabricating a photodiode.
 - 40. A method as defined in claim 35, further comprising fabricating a reset transistor disposed to reset the sense node.
 - 41. A method as defined in claim 35, further comprising fabricating an output amplifier coupled to the sense node.
 - 42. A method as defined in claim 41, wherein fabricating an output amplifier comprises fabricating a source follower amplifier.
 - 43. A method of manufacturing an imager cell, the method comprising: fabricating a photoreceptor in a semiconductor substrate;
- fabricating a sense node in the substrate; and

fabricating a pinned transfer gate in the substrate disposed to transfer charge between the photoreceptor and the sense node; and

fabricating a photoreceptor readout gate disposed above the photoreceptor, the photoreceptor readout gate having material removed to form a photoreceptor readout gate light aperture above the photoreceptor.

- 44. A method as defined in claim 43, further comprising fabricating a pinned aperture region under the photoreceptor readout gate light aperture.
- 45. A method as defined in claim 43, wherein fabricating the pinned transfer gate comprises fabricating an n-doped transfer region and fabricating a p-doped pinned region in the n-doped transfer region.

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- 46. A method as defined in claim 43, wherein fabricating a photoreceptor comprises fabricating a photogate.
- 47. A method as defined in claim 43, wherein fabricating a photoreceptor comprises fabricating a photodiode.
- 5 48. A method as defined in claim 43, further comprising fabricating a reset transistor disposed to reset the sense node.
 - 49. A method as defined in claim 43, further comprising fabricating an output amplifier coupled to the sense node.
 - 50. A method as defined in claim 49, wherein fabricating an output amplifier comprises fabricating a source follower amplifier.
 - 51. A method of manufacturing an imager cell, the method comprising:

fabricating a photoreceptor in a semiconductor substrate;

fabricating a sense node in the substrate; and

fabricating a pinned transfer gate in the substrate disposed to transfer charge between the photoreceptor and the sense node; and

fabricating, above the photoreceptor, a photoreceptor readout gate of a thickness less than 2000 Angstroms.

- 52. An method as defined in claim 51, wherein fabricating the pinned transfer gate comprises fabricating an n-doped transfer region and fabricating a p-doped pinned region in the n-doped transfer region.
- 53. An method as defined in claim 51, wherein fabricating a photoreceptor comprises fabricating a photogate.
- 54. An method as defined in claim 51, wherein fabricating a photoreceptor comprises fabricating a photodiode.

- 55. An method as defined in claim 51, further comprising fabricating a reset transistor disposed to reset the sense node.
- 56. An method as defined in claim 51, further comprising fabricating an output amplifier coupled to the sense node.
- 5 57. An method as defined in claim 57, wherein fabricating an output amplifier comprises fabricating a source follower amplifier.
 - 58. An imager cell comprising:

 means for detecting incident photons;

 means for storing transferred charge for readout; and
 - a pinned transfer gate disposed to transfer charge between the means for detecting and the means for storing.
 - 59. An imager cell as defined in claim 58, wherein the pinned transfer gate comprises a p-doped pinned region in an n-doped transfer region.
 - 60. An imager cell as defined in claim 58, further comprising means for transferring charge from the means for detecting incident photons to the pinned transfer gate.
 - 61. An imager cell as defined in claim 58, further comprising means for resetting the means for storing transferred charge.
 - 62. An imager cell as defined in claim 58, further comprising means for amplifying the transferred charge.
- 20 63. An imager cell as defined in claim 60, further comprising means for clocking the means for transferring charge.
 - 64. An imager cell as defined in claim 63, wherein the means for clocking is characterized by a V+ level applied during an integration period, and a V- level applied during a readout transfer period.

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- 65. An imager cell as defined in claim 60, wherein the means for transferring charge comprises a photoreceptor readout gate characterized by a thickness of less than 2000 Angstroms.
- 66. An imager cell as defined in claim 61, wherein the means for transferring charge comprises a photoreceptor readout gate characterized by a thickness of less than 1000 Angstroms.
 - 67. An imager cell as defined in claim 61, wherein the means for transferring charge comprises a photoreceptor readout gate characterized by a thickness of less than 500 Angstroms.
 - 68. An imager cell as defined in claim 60, wherein the means for transferring charge comprises a photoreceptor readout gate having material removed to form a photoreceptor readout gate light aperture above the means for detecting incident photons.
 - 69. An imager cell as defined in claim 68, further comprising a pinned aperture region under the photoreceptor readout gate light aperture.
- 15 70. An imaging array comprising:

an array of imager cells, each imager cell comprising a photoreceptor, a sense node, and a photoreceptor readout gate; and wherein at least one of the imager cells further comprises a pinned transfer gate disposed to transfer charge between the photoreceptor and the sense node; and

control circuitry coupled to each photoreceptor readout gate for supplying a photoreceptor readout clock simultaneously to a set of photoreceptors in the array,

whereby accumulated charge in each photoreceptor is transferred to its sense node to provide a snapshot of an image acquired by the imaging array.

71. An imager cell comprising:

- a photoreceptor including a photoreceptor readout gate;
- a sense node;
- a pinned transfer gate disposed to transfer charge between the photoreceptor and the sense node; and

control circuitry coupled to the photoreceptor readout gate for applying a photoreceptor readout clock to the photoreceptor readout gate, the photoreceptor readout clock comprising an integration period characterized by an integration voltage selected from a plurality of predetermined integration voltages to setup a preselected charge capacity level in the photoreceptor.